

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to : Commissioner for Patents, P. O. Box 1450, Alexandria, VA 22313-1450, on



Karen Cy-mars 11/5/03
(Signature & date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of _____ : November 5, 2003

Delehanty et al. _____ : Group Art Unit:

Serial No. 10/605,610:

Examiner:

Filed: 10-13-03 _____ :

International Business Machines Corporation
2070 Route 52
Hopewell Junction, NY 12533

TITLE: PLANARIZATION SYSTEM AND METHOD USING A CARBONATE CONTAINING FLUID

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to the duty of disclosure set forth in 37 C.F.R. 1.56, and further pursuant to the provisions of 37 C.F.R. 1.97 and 1.98, applicants hereby respectfully submit copies of the non-US patents and publications as listed on Form PTO-1449, are attached hereto.

In citing these documents, no representation is made nor intended as to the pertinency or non-pertinency of the art, that better art than that listed is not available, or that other art is not applicable.

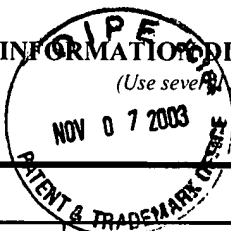
No fee is believed to be due for this submission. If any fees are required, however, the Commissioner is hereby authorized to charge such fees to Deposit Account No. 09-0458.

Respectfully submitted,

Todd M. C. Li
Todd M. C. Li
Registration No. 45,554
Telephone No. 845-894-6919

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)



Docket Number (Optional)

FIS9-2002-0214US1

Application Number

10/605,610

Applicant(s)

Delehanty et al.

Filing Date

10-13-03

Group Art Unit

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Appl. No. 60/463,358, Attorney Docket No. AMAT/7662L/CMP/CMP/RKK, entitled "Carbonation of ph controlled KOH solution for improved polishing of oxide films on semiconductor wafers"

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.